

Gleb A Iankevich

List of Publications by Year in descending order

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Version: 2024-02-01

12
papers

86
citations

1684188

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1474206

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12
all docs

12
docs citations

12
times ranked

56
citing authors

#	ARTICLE	IF	CITATIONS
1	High-temperature etching of SiC in SF ₆ /O ₂ inductively coupled plasma. Scientific Reports, 2020, 10, 19977.	3.3	29
2	Monocrystalline Quartz ICP Etching: Road to High-Temperature Dry Etching. Plasma Chemistry and Plasma Processing, 2020, 40, 423-431.	2.4	13
3	The effect of a lithium niobate heating on the etching rate in SF ₆ ICP plasma. Materials Research Express, 2019, 6, 046306.	1.6	12
4	Magnetotransport Properties of Ferromagnetic Nanoparticles in a Semiconductor Matrix Studied by Precise Size-Selective Cluster Ion Beam Deposition. Nanomaterials, 2020, 10, 2192.	4.1	7
5	Artificial synapses based on Josephson junctions with Fe nanoclusters in the amorphous Ge barrier. Journal of Applied Physics, 2022, 131, 073902.	2.5	7
6	Deep Etching of LiNbO ₃ Using Inductively Coupled Plasma in SF ₆ -Based Gas Mixture. Journal of Microelectromechanical Systems, 2021, 30, 90-95.	2.5	5
7	Corona discharge plasma application for the deposition of nanocomposite coatings. Materials Today: Proceedings, 2020, 30, 404-407.	1.8	4
8	Silicon carbide dry etching technique for pressure sensors design. Journal of Manufacturing Processes, 2022, 73, 316-325.	5.9	4
9	OES diagnostics as a universal technique to control the Si etching structures profile in ICP. Scientific Reports, 2022, 12, 5287.	3.3	4
10	ICP etching of SiC with low surface roughness. Materials Today: Proceedings, 2020, 30, 512-515.	1.8	1
11	Aerosol-Assisted Chemical Deposition of Nanocomposite Material in the "Iron-Carbon-Oxygen" System. Key Engineering Materials, 2019, 822, 320-326.	0.4	0
12	Registration of an ICP Plasma CV Dependences under Various Pressures in the Plasma-Chemical Deep Etching System. Key Engineering Materials, 2019, 822, 587-593.	0.4	0